T	1111	Search Text	DB	Time stamp
L Number	Hits	SealCh lext		11mc Scamp
1	7715	((438/637) or (438/622) or (438/624) or	USPAT;	2004/05/24
		(438/723) or (438/724) or (438/725) or	US-PGPUB;	15:02
,		(438/738) or (438/743) or	EPO; JPO; DERWENT;	
		(438/744)).CCLS.	IBM TDB	
2	0	("land(cap\$4adjlayer)").PN.	USPAT;	2004/05/24
		(US-PGPUB;	15:04
			EPO; JPO;	1
			DERWENT;	
_	597	(((438/637) or (438/622) or (438/624) or	IBM_TDB USPAT;	2004/05/24
3	391	(438/723) or (438/724) or (438/725) or	US-PGPUB;	15:25
		(438/738) or (438/743) or	EPO; JPO;	
		(438/744)).CCLS.) and (cap\$4 adj layer)	DERWENT;	
			IBM_TDB	0004/05/04
4	271	((((438/637) or (438/622) or (438/624) or	USPAT;	2004/05/24 15:05
		(438/723) or (438/724) or (438/725) or (438/738) or (438/743) or	US-PGPUB; EPO; JPO;	15:05
		(438/744)).CCLS.) and (cap\$4 adj layer))	DERWENT;	
		and (plasma same etch\$3 same (dielectric	IBM_TDB	
	1	or insulat\$3))	_	
5	63		USPAT;	2004/05/24
	-	or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or	US-PGPUB; EPO; JPO;	15.00
		(438/744)).CCLS.) and (cap\$4 adj layer))	DERWENT;	
		and (plasma same etch\$3 same (dielectric	IBM_TDB	
		or insulat\$3))) and (plasma same etch\$3	_	
	0.5	same (cap\$3 adj layer))	**************************************	2004/05/24
6	85	(((((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/725) or	USPAT; US-PGPUB;	2004/05/24
· .		(438/738) or (438/743) or	EPO; JPO;	15.25
		(438/744)).CCLS.) and (cap\$4 adj layer))	DERWENT;	·
		and (plasma same etch\$3 same (dielectric	IBM_TDB	
ļ.		or insulat\$3))) and (plasma same etch\$3	*	
].		same (cap\$3 adj layer) same polymer or residu\$2)		
7	17		USPAT;	2004/05/24
		or (438/723) or (438/724) or (438/725) or	US-PGPUB;	15:07
		(438/738) or (438/743) or	EPO; JPO;	
		(438/744)).CCLS.) and (cap\$4 adj layer))	DERWENT;	
		and (plasma same etch\$3 same (dielectric or insulat\$3))) and (plasma same etch\$3	IBM_TDB	
		same (cap\$3 adj layer))) and (plasma same		
	,	etch\$3 same (cap\$3 adj layer) same		۸ ,
		polymer or residu\$2)		
8	16		USPAT;	2004/05/24 15:07
		or (438/723) or (438/724) or (438/725) or (438/738) or (438/743) or	US-PGPUB; EPO; JPO;	13.07
		(438/744)).CCLS.) and (cap\$4 adj layer))	DERWENT;	
		and (plasma same etch\$3 same (dielectric	IBM_TDB]
		or insulat\$3))) and (plasma same etch\$3		
		same (cap\$3 adj layer))) and (plasma same etch\$3 same (cap\$3 adj layer) same		
		polymer or residu\$2)) and (oxygen or		
		"o.sub.2")		
9	5	(((((((438/637) or (438/622) or (438/624)	USPAT;	2004/05/24
1		or (438/723) or (438/724) or (438/725) or	US-PGPUB;	15:08
		(438/738) or (438/743) or	EPO; JPO; DERWENT;	
-		(438/744)).CCLS.) and (cap\$4 adj layer)) and (plasma same etch\$3 same (dielectric	IBM TDB	
		or insulat\$3))) and (plasma same etch\$3		
		same (cap\$3 adj layer))) and (plasma same		
		etch\$3 same (cap\$3 adj layer) same	1 .	
		polymer or residu\$2)) and ((oxygen or		the section of the designation of the section of th
		"o.sub.2") same (sio or (silicon adjoxide)))		
L	<u> </u>	1	·	

				T 0 0 0 4 / 2 = 12 * .
10	5	((((((((438/637) or (438/622) or (438/624) or (438/723) or (438/724) or (438/724) or	USPAT; US-PGPUB;	2004/05/24 15:08
		(438/725) or (438/738) or (438/743) or (438/744)).CCLS.) and (cap\$4 adj layer))	EPO; JPO; DERWENT;	
	ļ.	and (plasma same etch\$3 same (dielectric	IBM TDB	
		or insulat\$3))) and (plasma same etch\$3	_	
		<pre>same (cap\$3 adj layer))) and (plasma same</pre>		•
		etch\$3 same (cap\$3 adj layer) same		
		polymer or residu\$2)) and (oxygen or "o.sub.2")) and ((oxygen or "o.sub.2")		
	. :	same (sio or (silicon adj oxide)))		
1 .	2	((((((((438/637) or (438/622) or	USPAT;	2004/05/24
		(438/624) or (438/723) or (438/724) or	US-PGPUB;	15:22
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	
		(438/744)).CCLS.) and (cap\$4 adj layer)) and (plasma same etch\$3 same (dielectric	DERWENT; IBM TDB	
		or insulat\$3))) and (plasma same etch\$3	12122	·
		same (cap\$3 adj layer))) and (plasma same		
		etch\$3 same (cap\$3 adj layer) same		
		polymer or residu\$2)) and (oxygen or	<u> </u>	
		"o.sub.2")) and ((oxygen or "o.sub.2") same (sio or (silicon adj oxide)))) and		
		clean\$3		
	1	((((((((438/637) or (438/622) or	USPAT;	2004/05/24
		(438/624) or (438/723) or (438/724) or	US-PGPUB;	15:24
		(438/725) or (438/738) or (438/743) or	EPO; JPO; DERWENT;	
		(438/744)).CCLS.) and (cap\$4 adj layer)) and (plasma same etch\$3 same (dielectric	IBM TDB	
		or insulat\$3))) and (plasma same etch\$3	1511_155	
		same (cap\$3 adj layer))) and (plasma same		,
		etch\$3 same (cap\$3 adj layer) same		
		polymer or residu\$2)) and (oxygen or		
		"o.sub.2")) and ((oxygen or "o.sub.2") same (sio or (silicon adj oxide)))) and		
		((clean\$3 or remove) near10 (silicon adj		
		oxide))		1
	602	((438/902) or (438/906) or	USPAT;	2004/05/24
		(438/963)).CCLS.	US-PGPUB;	15:25
	•		EPO; JPO; DERWENT;	
			IBM TDB	
	56		USPAT;	2004/05/24
		(438/963)).CCLS.) and (cap\$4 adj layer)	US-PGPUB;	15:25
			EPO; JPO; DERWENT;	,
		, ,	IBM TDB	, ,
	0	((((438/902) or (438/906) or	USPAT;	2004/05/24
		(438/963)).CCLS.) and (cap\$4 adj layer))	US-PGPUB;	15:26
		and (plasma same etch\$3 same (cap\$3 adj	EPO; JPO;	
		layer) same (polymer or residu\$2))	DERWENT; IBM TDB	
	7518	((438/677) or (438/637) or (438/622) or	USPAT;	2004/05/24
		(438/624) or (438/723) or (438/724) or	US-PGPUB;	15:02
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	•
•		(438/744)).CCLS.	DERWENT;	
	273	(((438/677) or (438/637) or (438/622) or	IBM_TDB USPAT;	2003/12/09
	4/3	((438/624) or (438/723) or (438/724) or	US-PGPUB;	02:13
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	
		(438/744)).CCLS.) and (capping adj layer)	DERWENT;	
	1	/////20/6777	IBM_TDB	2002/12/00
4	175	((((438/677) or (438/637) or (438/622) or (438/624) or (438/723) or (438/724) or	USPAT; US-PGPUB;	2003/12/09 02:14
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	02.13
	1	(438/744)).CCLS.) and (capping adj	DERWENT;	
		layer)) and (etch\$3 same (capping adj	IBM_TDB	
	1	laveri	1	

	·	1/1/1/20/677\ on 1/20/627\ on 1/20/622\	USPAT;	2003/12/09
-	61	(((((438/677) or (438/637) or (438/622)	US-PGPUB;	02:14
X		or (438/624) or (438/723) or (438/724) or		02:14
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	
		(438/744)).CCLS.) and (capping adj	DERWENT;	
		layer)) and (etch\$3 same (capping adj	IBM_TDB	
		layer))) and (plasma same oxygen)		/ /
_ `	4	(((((((438/677) or (438/637) or (438/622))	USPAT;	2003/12/09
		or (438/624) or (438/723) or (438/724) or	US-PGPUB;	02:15
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	
	•	(438/744)).CCLS.) and (capping adj	DERWENT;	
	_	layer)) and (etch\$3 same (capping adj	IBM_TDB	
,		layer))) and (plasma same oxygen)) and	_	·
		clean\$3) and ((in adj2 situ) or (ex adj2		
		situ))		·
_	32	((((((438/677) or (438/637) or (438/622)	USPAT;	2003/12/09
	32	or (438/624) or (438/723) or (438/724) or	US-PGPUB;	15:59
		(438/725) or (438/738) or (438/743) or	EPO; JPO;	
		(438/744)).CCLS.) and (capping adj	DERWENT;	
		layer)) and (etch\$3 same (capping adj	IBM TDB	
		layer))) and (plasma same (capping ad)	1011_100	
	· .	clean\$3		
		(((((438/677) or (438/637) or (438/622)	USPAT;	2003/12/09
_	0	(((((438/6//) OF (438/63/) OF (438/622)	US-PGPUB;	15:59
		or (438/624) or (438/723) or (438/724) or	EPO; JPO;	15.59
	1	(438/725) or (438/738) or (438/743) or		
		(438/744)).CCLS.) and (capping adj	DERWENT;	!
		layer)) and (etch\$3 same (capping adj	IBM_TDB	`
		layer))) and (plasma same oxygen)) same		
		clean\$3		0000/10/00
-	1025	clean\$3 same(contact or via) same oxygen	USPAT;	2003/12/09
		same plasma	US-PGPUB;	16:00
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_ '	548	(clean\$3 same(contact or via) same oxygen	USPAT;	2003/12/09
		same plasma) and 438/\$.ccls.	US-PGPUB;	16:01
			EPO; JPO;	
	1		DERWENT;	
		·	IBM TDB	
_	49	((clean\$3 same(contact or via) same	USPAT;	2003/12/09
		oxygen same plasma) and 438/\$.ccls.) and	US-PGPUB;	16:01
		((cap or capping) adj layer)	EPO; JPO;	
		(Verb or embrana) and raiori	DERWENT;	
	1		TBM TDB	